A	pplication No.	Applicant(s)	
10	0/813,784	HUANG, CHIEN-CHAO	
Notice of Allowability	xaminer	Art Unit	
Н	sien-ming Lee	2823	
The MAILING DATE of this communication appears claims being allowable, PROSECUTION ON THE MERITS IS (OF rewith (or previously mailed), a Notice of Allowance (PTOL-85) or OTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHT the Office or upon petition by the applicant. See 37 CFR 1.313 and the Office of the control of	R REMAINS) CLOSED in to other appropriate communities. This application is sub-	his application. If not included ication will be mailed in due could	rse. THIS
☑ This communication is responsive to <u>5/24/2006</u> .			
☑ The allowed claim(s) is/are <u>1-7,9-18,20-25,27-35,37-41 and 4</u>	<u>3-48</u> .		
 Acknowledgment is made of a claim for foreign priority under a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have be 		(f) .	
Certified copies of the priority documents have be Certified copies of the priority documents have be		No	
Copies of the certified copies of the priority documents of the priority documents of the priority documents.			from the
International Bureau (PCT Rule 17.2(a)).			.
* Certified copies not received:			•
Applicant has THREE MONTHS FROM THE "MAILING DATE" of to noted below. Failure to timely comply will result in ABANDONMEN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	IT of this application.		
A SUBSTITUTE OATH OR DECLARATION must be submitted INFORMAL PATENT APPLICATION (PTO-152) which gives recommended in the submitted in the submi			CE OF
CORRECTED DRAWINGS (as "replacement sheets") must be	e submitted.		
(a) \square including changes required by the Notice of Draftsperson'	's Patent Drawing Review (PTO-948) attached	
1) hereto or 2) to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Ar Paper No./Mail Date	mendment / Comment or ir	the Office action of	
Identifying indicia such as the application number (see 37 CFR 1.84(each sheet. Replacement sheet(s) should be labeled as such in the h			k) of
. DEPOSIT OF and/or INFORMATION about the deposit of attached Examiner's comment regarding REQUIREMENT FOR			the
ttachment(s) Notice of References Cited (PTO-892)	5 🗆 Notice of lefe	rmal Patent Application (PTO-15	52)
☐ Notice of References Cited (PTO-992) ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Sun	···	14)
☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08),	Paper No./M	ail Date mendment/Comment	
Paper No./Mail Date Examiner's Comment Regarding Requirement for Deposit	8. ⊠ Examiner's S	tatement of Reasons for Allowar	nce
of Biological Material	9. Other		
		HSIEN-MING LEE	D
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DETAILED ACTION

Remarks

- 1. The objection and rejections, as set forth in the final rejection, have been withdrawn in response to applicant's amendment filed 5/24/2006.
- 2. Applicant's cancellation to claims 8, 19, 26, 36 and 42 is acknowledged. Claims 1-7, 9-18, 20-25, 27-35, 37-41 and 43-48 are pending in the application.

Examiner's Amendment

3. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Randy W. Tung (Reg. No. 31,311) on May 30, 2006.

4. The application has been amended as follows:

In claim 1, at line 11 (i.e. in e step), replace "said AlCu portion" with -- said portion of said AlCu layer --.

In claim 9, at line 1, replace "method 8" with -- method 1 --.

In claim 10, at line 1, replace "method 8" with -- method 1 --.

In claim 15, at line 2, replace "pressures" with -- pressure --.

In claim 22, at line 3, replace "PMD" with – pre-metal dielectric --.

Allowable Subject Matter

5. Claims 1-7, 9-18, 20-25, 27-35, 37-41 and 43-48 are allowed.

6. The following is an examiner's statement of reasons for allowance:

In re claim 1, the prior art of record, either alone or combination, does not teach or suggest forming a layer of AlCu filling a via opening in closed communication with a conductive portion, wherein the conductive portion comprises silicide electrical contact areas comprising a CMOS transistor portion selected from the group consisting of a gate electrode and source and drain regions; and carry out process steps c) and d) at a temperature of less than about 400 degrees Centigrade.

In re claim 13, the prior art of record, either alone or combination, does not teach or suggest that a conductive portion comprises salicide electrical contact areas comprising a CMOS transistor portion; forming a layer of AlCu at a temperature less than 400 °C to fill a via opening to form an AlCu via; and forming an AlCu interconnect line from the portion of the AlCu layer.

In re claim 24, the prior art of record, either alone or combination, does not teach or suggest that an AlCu via comprises a first barrier layer formed in a dielectric insulating layer in closed with communication with a conductive portion, wherein the conductive portion selected from the group consisting of tungsten, metal silicide, copper and AlCu; and a second barrier layer encapsulates an AlCu interconnect line on three sides.

In re claim 35, the prior art of record, either alone or combination, does not teach or suggest that an *AlCu via comprises a barrier layer* lining in an AlCu via opening, the via opening formed in a dielectric insulating layer in *closed with communication with a conductive portion*; and structure portions b is stacked *sequentially* in overlying dielectric layers to comprises at least *three* metallization layers.

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7. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for

Allowance."

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hsien-ming Lee whose telephone number is 571-272-1863. The examiner can normally be reached on Tuesday-Thursday $(7:30 \sim 6:00)$.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Hsien-ming Lee Primary Examiner Art Unit 2823

HSIEN-MING LEE PRIMARY EXAMINER 5/30/06

May 30, 2006